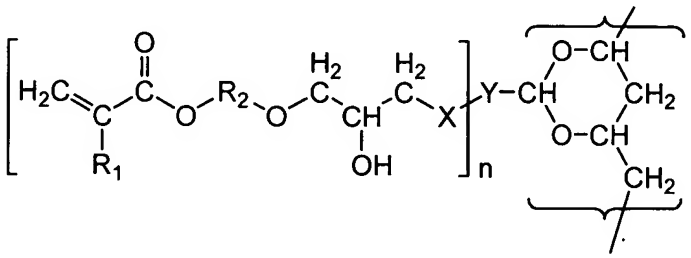
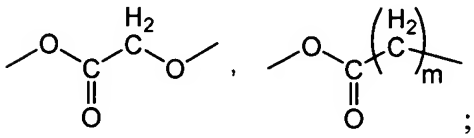
A) Amendments to the claims:

1. (currently amended) A saponified poly(vinyl acetate)-based photosensitive resin characterized by having a structural unit represented by formula (1):



(1)

(wherein R_1 represents H or Me; R_2 represents a linear or branched C2-C10 alkylene group; n is an integer of 1 to 3; X represents



;

m is an integer of 0 to 6; and Y represents an aromatic ring or a single bond).

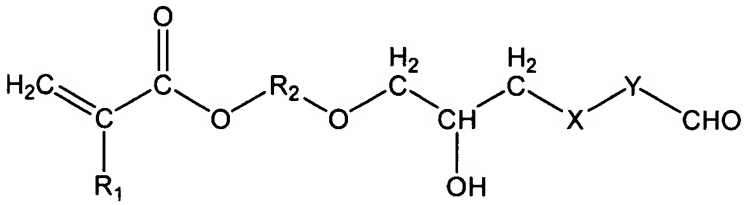
2. (original) A photosensitive resin composition comprising a photosensitive resin according to claim 1.

3. (original) A photosensitive resin composition according to claim 2, which further comprises at least one photopolymerization initiator.

4. (currently amended) A photosensitive resin composition according to claim 2 ~~or 3~~, which further comprises water.

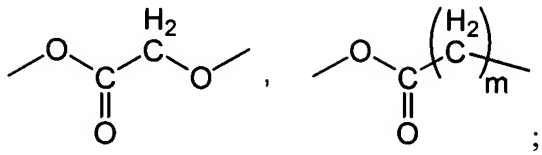
5. (currently amended) A method for forming a hydrogel comprising subjecting a photosensitive resin composition as recited in ~~any of~~ claims 2 ~~to 4~~ to photopolymerization.

6. (currently amended) A compound represented by formula (2):



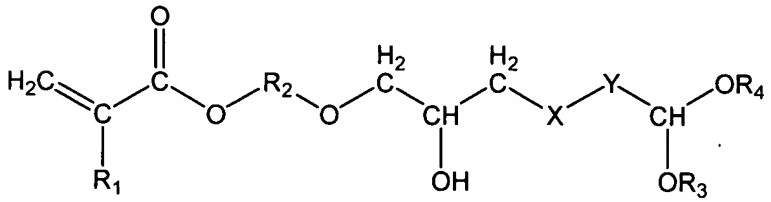
(2)

(wherein R_1 represents H or Me; R_2 represents a linear or branched C2-C10 alkylene group; X represents



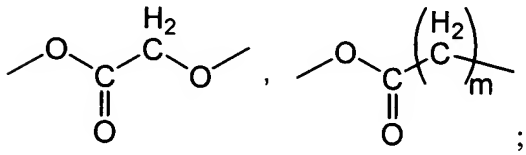
m is an integer of 0 to 6; and Y represents an aromatic ring or a single bond).

7. (currently amended) A compound represented by formula (3):



(3)

(wherein R_1 represents H or Me; R_2 represents a linear or branched C2-C10 alkylene group; X represents



m is an integer of 0 to 6; Y represents an aromatic ring or a single bond; and each of R_3 and R_4 represents a C1-C3 alkyl group).

8. (new) A photosensitive resin composition according to claim 3, which further comprises water.

9. (new) A method for forming a hydrogel comprising subjecting a photosensitive resin composition as recited in claim 3 to photopolymerization.

10. (new) A method for forming a hydrogel comprising subjecting a photosensitive resin composition as recited in claim 4 to photopolymerization.